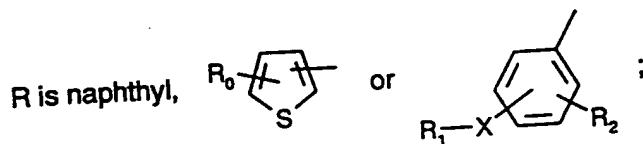
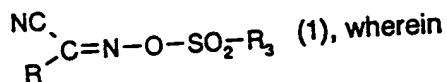


Abstract of the Disclosure

The invention describes the use of oxime alkyl sulfonate compounds of formula 1



$\text{R}_0$  is either an  $\text{R}_1\text{-X}$  group or  $\text{R}_2$ ;

$\text{X}$  is a direct bond, an oxygen atom or a sulfur atom;

$\text{R}_1$  is hydrogen,  $\text{C}_1\text{-C}_4$ alkyl or a phenyl group which is unsubstituted or substituted by a substituent selected from the group consisting of chloro, bromo,  $\text{C}_1\text{-C}_4$ alkyl and  $\text{C}_1\text{-C}_4$ alkyloxy;

$\text{R}_2$  is hydrogen or  $\text{C}_1\text{-C}_4$ alkyl; and

$\text{R}_3$  is straight-chain or branched  $\text{C}_1\text{-C}_{12}$ alkyl which is unsubstituted or substituted by one or more than one halogen atom;

as photosensitive acid generator in a chemically amplified photoresist which is developable in alkaline medium and which is sensitive to radiation at a wavelength of 340 to 390 nanometers and correspondingly composed positive and negative photoresists for the above-mentioned wavelength range.